



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Trung T. Doan

Serial No.: 09/133,989

Filed: August 14, 1998

For: CHEMICAL DISPENSING SYSTEM FOR  
SEMICONDUCTOR WAFER PROCESSING

§  
§ Group Art Unit: 1734  
§  
§ Examiner: L. Edwards  
§  
§ Atty. Docket: 93-0421.03  
§  
§  
§  
§

#15/D  
TL 9-6-01

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AMENDMENT AND RESPONSE TO THE  
OFFICE ACTION OF FEBRUARY 28, 2001

Commissioner for Patents  
Washington, D.C. 20231

Certificate of Mailing (37 C.F.R. § 1.8)

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail, postage prepaid, in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231, on the date below:

8-28-01  
Date

*Irish Thomas-Haides*  
Signature

Dear Sir:

Per the Examiner's Office Action of February 28, 2001, please amend the above-captioned application as follows.

IN THE CLAIMS

Please rewrite the appropriate claim to the form indicated below.

20. (Thrice amended) A material removal system for a wafer, comprising:

a negative pressure device defining a vacuum area on more than one side of said wafer

while said device is in an operational position; and

a solvent dispenser intersecting said vacuum area and aligned with an edge of said wafer

while said device is in said operational position.

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